



Patent Application No. 10/714,304
Customer Number: 42717
Reply to Office action of August 23, 2005

DPW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Chao-Cheng Chen, et al.	§	Docket No.:	24061.475 / 2002-0210
Serial No.:	10/714,304	§	Examiner:	Michelle Estrada
Filed:	November 14, 2003	§	Art Unit:	2823
For:	Dual Damascene Process Flow	§	Conf. No.:	2110
	for Porous Low-K Materials	§		

Commissioner for Patents
Mail Stop Amendment
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

Dear Sir:

In response to the Final Office Action of August 23, 2005, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 11 of this paper.